

	Hits	Search Text	DBs
22	2	<p>((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same (uniform\$3 or thin\$4 or etch\$4) same micron) and</p> <p>((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 (liberat\$4 or generat\$4)) or PAG or photo\$8generat\$4) near9 (increas\$4 or var\$5 or chang\$4 adjust\$4 or alter\$4 or control\$4)) same (moiet\$4 or group or (function\$3 near4 group))) and ((fluoro\$4polymer\$4 or ((fluor\$4 or halogen) near9 (polymer or carbon)) or (SOG near6 (organic or resist))) same (pattern\$4 or lithograph\$6 or photolithograph\$8 or expos\$4 or mask))</p>	<p>US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB</p>

	Hits	Search Text	DBs
23	46	<p>((resist or photoresist or photosensitive or radiation\$4sensitive or photocur\$4) same (photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 generat\$4) or PAG or photo\$8generat\$4) same (coat\$4 or spin\$4coat\$4 or deposit\$4) same (uniform\$3 or thin\$4 or etch\$4) same (resolution or imag\$4 or thickness or micron)) and (((photo\$4active\$4acid\$4generat\$4 or (photoacid near5 (liberat\$4 or generat\$4)) or (acid near5 (liberat\$4 or generat\$4)) or PAG or photo\$8generat\$4) near9 (increas\$4 or var\$5 or chang\$4 adjust\$4 or alter\$4 or control\$4)) same (moiet\$4 or group or (function\$3 near4 group)))</p>	<p>US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB</p>